

Supplementary

Selected ZnO ALD thin films were investigated with helium ion microscopy (HIM). Samples were cleaved and imaged at 45° angle with 30 keV helium beam. Images of the ZnO films deposited with diethylzinc (DEZ) and normal water, $^1\text{H}_2\text{O}$, at different deposition temperatures are presented in Fig. S1. For comparison, similar images of the ZnO films deposited with heavy water, $^2\text{H}_2\text{O}$, are shown in Fig. S2.

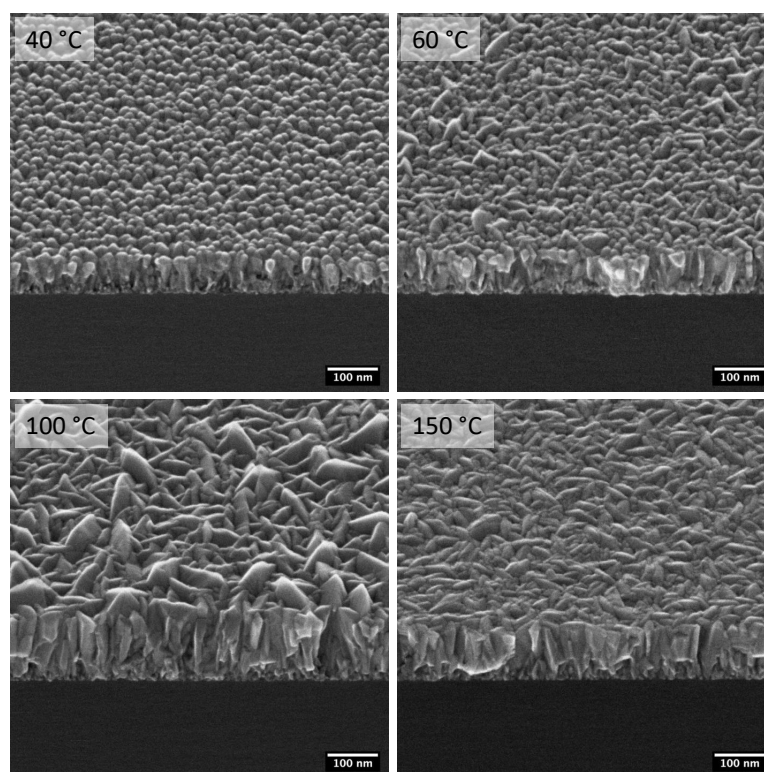


Figure S1: HIM images of the cleaved ZnO films on top of the Si-substrate deposited with DEZ and $^1\text{H}_2\text{O}$ at different deposition temperatures.

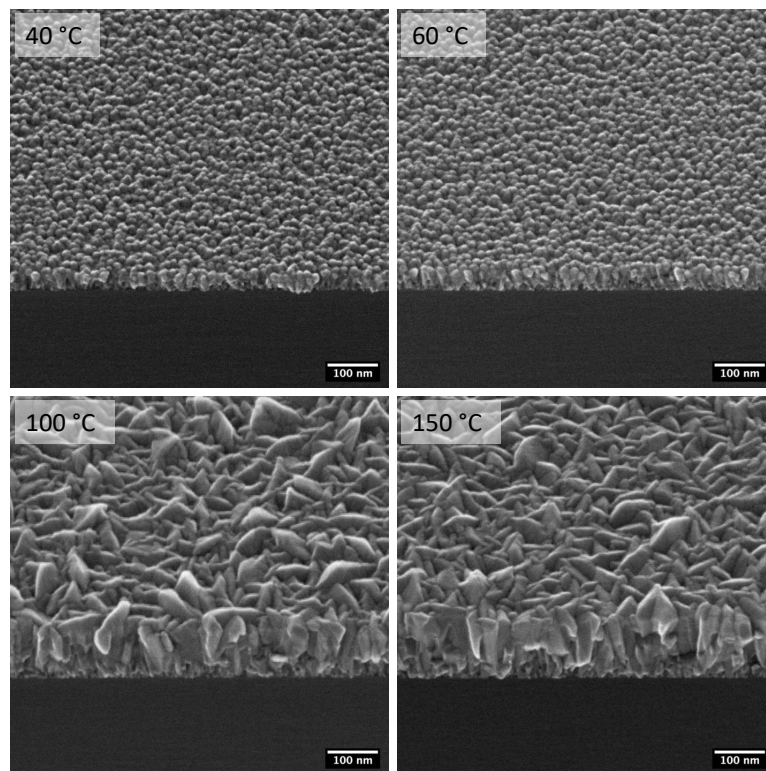


Figure S2: HIM images of the cleaved ZnO films on top of the Si-substrate deposited with DEZ and $^2\text{H}_2\text{O}$ at different deposition temperatures.